SU8 Developer Use

The CEPSR Clean Room stores and supplies one gallon bottles of SU8 developer. The bottles are located in the small and large yellow rooms under the fume hoods. They are placed with other solvents and developers. SU-8 2000 photoresist has been designed for use in immersion, spray or spray-puddle processes with this developer. Strong agitation is recommended when developing high aspect ratio and/or thick film structures such as small holes with small or tight pitch.

**Process**

*Note:* Variables including such parameters as developing/rinsing time as well as choice of resist should be optimized.

1) Remove SU8 bottle from cabinet under the fume hood and prepare two separate beakers filled with SU8 developer. Prepare your stopwatch.

2) After exposure and post baking your sample, fully immerse the substrate into the developer and simultaneously start your stopwatch (you can sonicate or manually agitate the solution).

3) Remove your sample and immerse into second beaker for rinsing, usually for 10 seconds.

4) Take your sample out and rinse it with IPA for 10 seconds to halt the development process and to prevent scumming.

5) Blow dry your substrate with a nitrogen gun.

6) Any used SU8 developer should be properly discarded into the SU8 developer waste container, located in the cabinet below the fume hood.

7) Clean up your work station.